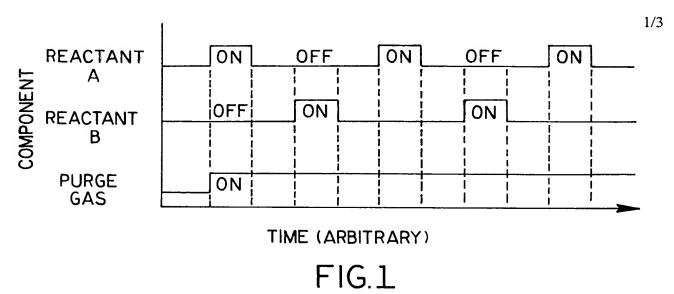
Inventor: Chih-Ta Wu

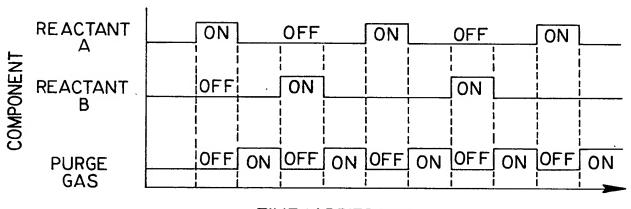
Serial No.: To Be Assigned Filed: Herewith

For: Atomic Layer Deposition (ALD) Method with Enhanced Deposition Rate

Attorney Doc. No.: 67,200-940



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TIME (ARBITRARY)

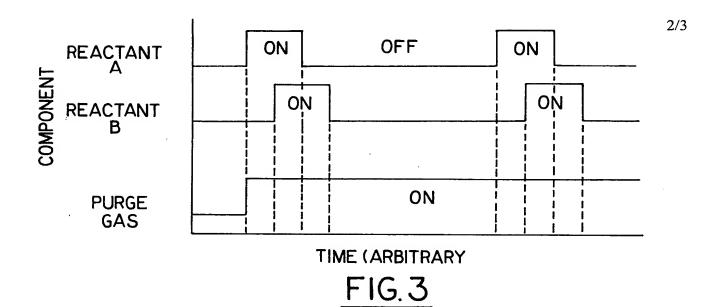
FIG.2

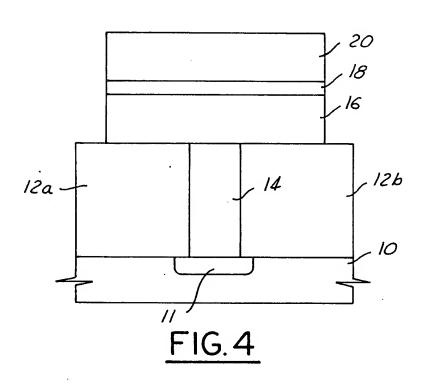
Inventor: Chih-Ta Wu

Serial No.: To Be Assigned Filed: Herewith

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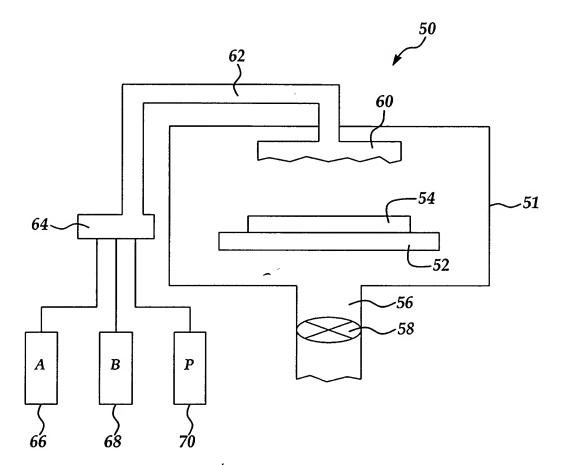


Figure 5

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